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Nanometrics Announces the NanoSpec II Film Metrology System for Advanced Material Characterization

MILPITAS, Calif., Dec. 2, 2014 (GLOBE NEWSWIRE) -- Nanometrics Incorporated (Nasdaq:NANO), a leading provider of advanced process control metrology and inspection systems, today announced the launch of its NanoSpec® II standalone metrology system, the latest model in its NanoSpec line of economic film metrology systems.

With a streamlined design based on the long-proven NanoSpec tabletop architecture, the NanoSpec II standalone is a fully automated non-contact optical metrology system for advanced material characterization on substrates up to 200mm. For films analysis, the NanoSpec II enables process control metrology and characterization on full-stack, multi-layer films and optical constant variation monitoring. New system hardware and software enhancements make the NanoSpec II the industry's most powerful and cost-effective film metrology system in its class, ideally suited for industrial and research environments.

"Our latest NanoSpec II standalone and tabletop systems continue to leverage our broad field applications experience across all types of thin film applications," commented David Doyle, vice president of the Materials Characterization Group at Nanometrics. "The NanoSpec II enables production and R&D customers to tackle their most advanced thin film metrology applications, all at a lower cost of ownership." For owners interested in upgrading their legacy tools, the NanoSpec II can seamlessly convert and upgrade existing measurement recipes.

The new NanoSpec II system will be introduced at the upcoming SEMICON Japan 2014 event being held December 3-5, 2014 at the Tokyo Big Sight, Tokyo, Japan. Nanometrics will be at booth 4168 in Hall 4.

About Nanometrics

Nanometrics is a leading provider of advanced, high-performance process control metrology and inspection systems used primarily in the fabrication of semiconductors and other solid-state devices, such as data storage components and discretes including high-brightness LEDs and power management components. Nanometrics' automated and integrated metrology systems measure critical dimensions, device structures, overlay registration, topography and various thin film properties, including film thickness as well as optical, electrical and material properties. The company's process control solutions are deployed throughout the fabrication process, from front-end-of-line substrate manufacturing, to high-volume production of semiconductors and other devices, to advanced wafer-scale packaging applications. Nanometrics' systems enable advanced process control for device manufacturers, providing improved device yield at reduced manufacturing cycle time, supporting the accelerated product life cycles in the semiconductor market. The company maintains its headquarters in Milpitas, California, with sales and service offices worldwide. Nanometrics is traded on NASDAQ Global Select Market under the symbol NANO. Nanometrics' website is <http://www.nanometrics.com>.

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